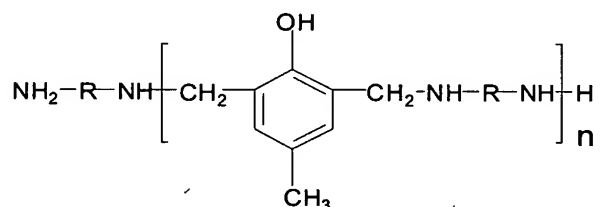


ABSTRACT OF THE DISCLOSURE

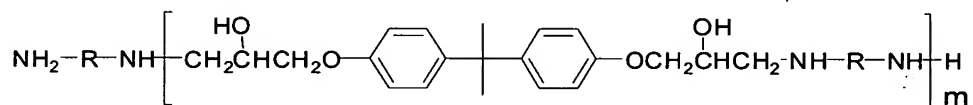
The present invention relates to an exfoliating agent and to a process for producing random form of nanoscale silica plates. Two types of exfoliating agents are applied in the present invention, which respectively have the formula:

AMO



where n=1 to 5

AEO



where m=1 to 5

wherein R is a polyoxypropylene group, polyoxyethylene/oxypropylene group, or polyethylene amino group. In this invention, layered silicate clays are exfoliated into random silica plates by acidifying AMO or AEO with inorganic acid, adding the acidified AMO or AEO to layered silicate clay with agitation, and adding sodium hydroxide or chloride of alkali metal or alkaline-earth metal, in ethanol, water and a hydrophobic organic solvent to the intermediate product and repeating phase separation procedures to isolate random silica plates from water phase.